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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/047,627	01/14/2002	Satoshi Yamamoto	113197-020	4034	
24573	7590 04/22/2004		EXAMINER		
BELL, BOYD & LLOYD, LLC PO BOX 1135			FERGUSON,	FERGUSON, MARISSA L	
	L 60690-1135		ART UNIT	PAPER NUMBER	
•			2854		

DATE MAILED: 04/22/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)	! •			
Office Action Summary		10/047,627	YAMAMOTO ET A	AL.			
		Examiner	Art Unit				
		Marissa L Ferguson	2854				
Period fo	The MAILING DATE of this communicat or Reply	ion appears on the cover sheet with	the correspondence ad	ldress			
A SH THE - Exte after - If the - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR MAILING DATE OF THIS COMMUNICA insions of time may be available under the provisions of 37 SIX (6) MONTHS from the mailing date of this communical period for reply specified above is less than thirty (30) date to period for reply is specified above, the maximum statutoure to reply within the set or extended period for reply will, reply received by the Office later than three months after the patent term adjustment. See 37 CFR 1.704(b).	TION. 7 CFR 1.136(a). In no event, however, may a repation. 1ys, a reply within the statutory minimum of thirty by period will apply and will expire SIX (6) MONTH by statute, cause the application to become ABA.	ly be timely filed (30) days will be considered timel HS from the mailing date of this on the constant of the	·. y. ommunication.			
Status							
1)🛛	Responsive to communication(s) filed o	n 12 January 2004					
2a)□	•	☐ This action is non-final.					
3)	Since this application is in condition for		rs, prosecution as to the	e merits is			
,	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposit	ion of Claims						
4)⊠	Claim(s) 1-11 is/are pending in the application. 4a) Of the above claim(s) 2,3 and 5-7 is/are withdrawn from consideration. Claim(s) is/are allowed. Claim(s) 1,4 and 8-11 is/are rejected. Claim(s) is/are objected to.						
,—							
5)[
6)⊠							
7)							
8)□	Claim(s) are subject to restriction	and/or election requirement.					
Applicat	ion Papers						
9)[The specification is objected to by the E	xaminer.					
10)⊠	0)⊠ The drawing(s) filed on <u>12 January 2004</u> is/are: a)⊠ accepted or b)⊡ objected to by the Examiner.						
	Applicant may not request that any objection	n to the drawing(s) be held in abeyanc	e. See 37 CFR 1.85(a).	•.			
	Replacement drawing sheet(s) including the	correction is required if the drawing(s) is objected to. See 37 Ci	FR 1.121(d).			
11)	The oath or declaration is objected to by	the Examiner. Note the attached	Office Action or form P	ΓΟ-152.			
Priority (under 35 U.S.C. § 119						
	Acknowledgment is made of a claim for	foreign priority under 35 U.S.C. & 1	119(a)-(d) or (f).				
<i>,</i> —		roroign phony and or or or or or	(.) (.) (.) .				
۵,	1.⊠ Certified copies of the priority do	cuments have been received.					
		cuments have been received in Ap	plication No	•			
		he priority documents have been re		Stage			
	application from the International	•		9			
* (See the attached detailed Office action for	• • • • • • • • • • • • • • • • • • • •	eceived.				
		,					
Attachmer	ntis)						
_	ce of References Cited (PTO-892)	4) 🗍 Interview Su	mmary (PTO-413)	•			
2) Notic	ce of Draftsperson's Patent Drawing Review (PTO-	.948) Paper No(s)	/Mail Date				
	mation Disclosure Statement(s) (PTO-1449 or PT0 er No(s)/Mail Date	D/SB/08) 5) Notice of Infe 6) Other:	ormal Patent Application (PT) -	U-152)			

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DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1,4 and 8-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ko (US Patent 5,528,452) in view of Tapani (EP 0,727,650).

Ko teaches a pressure sensor comprising a silicon structure having a conductive diaphragm (3), a silicon substrate bonded on a substrate, which comprises an electrode covered by a dielectric film (2), so that a diaphragm and an electrode are facing each other and there is a gap between a diaphragm and a dielectric film, a pressure sensor measuring a pressure applied thereto by detecting capacitance according to an area of a contact face of a diaphragm which touches a dielectric film when a pressure is applied and a silicon structure having a conductive diaphragm, provided by doping of an impurity and anisotropic etching (Admitted Disclosure of Description of Related Art, Page 1 and Page 2). However, he does not explicitly disclose a concentration of an impurity at a top face of a diaphragm being equal to or greater than 1x10¹⁹ cm⁻³ and less than 9x10¹⁹ cm⁻³ and an etch pit density on a top face of a diaphragm being equal to or less than five per μm².

Tapani teaches a diaphragm portion containing a boron impurity concentration (Column 3, Lines 39-57 and Column 4) and an etch pit (see element 12, Column 4,

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Lines 53-58 and column 5, Lines 1-8) that is used to insure adequate thickness of the diaphragm portion. It would obvious at the time the invention was made to a person having ordinary skill in the art to modify the invention as taught by Ko to include impurities and an etch pit as taught by Tapani, since Tapani teaches adding impurities for protection of the thin films and etch pits that act as transient overpressure protection for the diaphragms.

Ko and Tapani teach a range of impurity and etch pit densities, however they do not teach the specific range or value of the etch pit and impurity concentration as claimed. However, it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233. It would have been obvious to one having ordinary skill in the art at the time the invention was made to provide a specific range or value, since such a modification would result in the impurity concentration and etch pit densities providing a stronger, durable diaphragm structure.

Response to Arguments

2. Applicant's arguments with respect to claims 1 and 4 have been considered but are most in view of the new ground(s) of rejection.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Marissa L Ferguson whose telephone number is (571)

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272-2163. The examiner can normally be reached on (M-T) 6:30am-4:00pm and every other (F) 7:30am-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Andrew Hirshfeld can be reached on (571) 272-2168. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Marissa L Ferguson Examiner Art Unit 2854

MRS

ANDREW H. HIRSHFELD SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800